§ 98.96 Data reporting requirements.

In addition to the information required by §98.3(c), you must include in each annual report the following information for each electronics manufacturing facility:

(a) Annual manufacturing capacity of your facility as determined in Equation I–5 of this subpart.

(b) For facilities that manufacture semiconductors, the diameter of wafers manufactured at your facility (mm).

(c) Annual emissions of:

(1) Each fluorinated GHG emitted from each process type for which your facility is required to calculate emissions as calculated in Equations I–6 and I–7 of this subpart.

(2) Each fluorinated GHG emitted from each individual recipe (including those in a set of similar recipes), or process sub-type as calculated in Equations I–8 and I–9 of this subpart, as applicable.

(3) N₂O emitted from each chemical vapor deposition process and from other N₂O-using manufacturing processes as calculated in Equation I–10 of this subpart.

(4) Each fluorinated heat transfer fluid emitted as calculated in Equation I–16 of this subpart.

(d) The method of emissions calculation used in §98.93.

(e) Annual production in terms of substrate surface area (e.g., silicon, PV-cell, glass).

(f) When you use factors for fluorinated GHG process utilization and by-product formation rates other than the defaults provided in Tables I–3, I–4, I–5, I–6, and I–7 to this subpart and/or N₂O utilization factors other than the defaults provided in Table I–8 to this subpart, you must report the following, as applicable:

(1) The recipe-specific utilization and by-product formation rates for each individual recipe (or set of similar recipes) and/or facility-specific N₂O utilization factors.

(2) For recipe-specific utilization and by-product formation rates, the film or substrate that was etched/cleaned and the feature type that was etched, as applicable.

(3) Certification that the recipes included in a set of similar recipes are similar, as defined in §98.98.

(4) Certification that the measurements for all reported recipe-specific utilization and by-product formation rates and/or facility-specific N₂O utilization factors were made using the International SEMATECH #06126823A-ENG (incorporated by reference, see §98.7), or the International SEMATECH #01104197A–XFR (incorporated by reference, see §98.7) if measurements were made prior to January 1, 2007.

(5) Source of the recipe-specific utilization and by-product formation rates and/or facility-specific-N₂O utilization factors.